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EXPEDITED PROCEDURE - EXAMINING GROUP 2815

S/N 09/259,762

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Zhiping Yin et al.	Examiner:	Jose Diaz
Serial No.:	09/259,762	Group Art Unit:	2815
Filed:	March 1, 1999	Docket:	303.531US1
Title:	OXYGEN PLASMA TREATMENT FOR NITRIDE SURFACE TO REDUCE PHOTO FOOTING		

15/D
FJONES
8-20-02

SUPPLEMENTAL AMENDMENT & RESPONSE UNDER 37 C.F.R. § 1.116

Box AF
Commissioner for Patents
Washington, D.C. 20231

In response to the Final Office Action mailed May 6, 2002, and the Advisory Action mailed July 25, 2002, please amend the application as follows:

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IN THE CLAIMS

Please substitute the claim set in the appendix entitled Clean Version of Pending Claims for the previously pending claim set. The substitute claim set is intended to reflect amendment of previously pending claim 1. The specific amendments to individual claims are detailed in the following marked up set of claims.

1. (Amended) A method for reducing profile distortion in semiconductor fabrication without roughening a semiconductor substrate surface, comprising:
 - providing a semiconductor substrate comprising a film comprising silicon-nitride;
 - treating the film in a vacuum of about 3.0-6.5 Torr, for a time of about 10 seconds to about 5 minutes, and in an atmosphere substantially free of argon comprising oxygen plasma as the gas present in the greatest concentration wherein the oxygen plasma flow rate is at least about 300 sccm oxygen and the atmosphere renders the substrate resistant to profile distortion and roughening to make a treated substrate;
 - applying a resist to the treated substrate; and
 - patterning the resist.

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**REQUEST
FOR
CONTINUED EXAMINATION (RCE)
TRANSMITTAL**

Subsection (b) of 35 U.S.C. § 132, effective on May 29, 2000,
provides for continued examination of an utility or plant application
filed on or after June 8, 1995.

See The American Inventors Protection Act of 1999 (AIPA).

Application Number	09/259,762
Filing Date	March 1, 1999
First Named Inventor	Zhiping Yin et al.
Group Art Unit	2815
Examiner Name	Jose Diaz
Attorney Docket Number	303.531US1

This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application entitled OXYGEN PLASMA TREATMENT FOR NITRIDE SURFACE TO REDUCE PHOTO FOOTING.

Submission required under 37 C.F.R. § 1.114

1. ☐ Consider the amendment(s)/reply under 37 C.F.R. § 1.116 previously filed on ☐
2. ☐ Consider the arguments in the Appeal Brief or Reply Brief previously filed on ☐
3. ☒ A Supplemental Amendment Under 37 CFR § 1.116 (4 pages) is enclosed.
4. ☐ A new power of attorney (☐ pages) is enclosed.
5. ☐ An Information Disclosure Statement is enclosed (☐ pages)
 - a. ☐ Form(s) 1449
 - b. ☐ Copies of IDS Citations
6. ☒ A check in the amount of \$740.00 is attached to pay the RCE filing fee required under C.F.R. § 1.17(e).
7. ☒ The Commissioner is hereby authorized to credit overpayments or charge any fees set forth in 37 C.F.R. §§ 1.16 through 1.18 to Deposit Account No. 19-0743.
8. ☐ A petition for extension of time in the prior application (☐ pages) is enclosed along with a check in the amount of \$ to pay the extension fee.
9. ☒ Other: A Clean Version of Pending Claims (2 pages)

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Customer Number **21186**

CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: Commissioner for Patents, Box RCE, Washington, D.C. 20231, on this 6 day of August, 2002.

Tina Kohout
Name

Z. Kohout
Signature

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